Second Call for Papers

14 International Conference on Simulation of Semiconductor Processes and Devices

SISPAD2014

September 9 – 11, 2014 Workshop, September 8 Mielparque Yokohama, Yokohama, JAPAN

Co-sponsored by Japan Society of Applied Physics Technical co-sponsored by IEEE Electron Devices Society





Scope:

This conference provides an opportunity for the presentation and discussion of the latest advances in modeling and simulation of semiconductor devices, processes, and equipment for integrated circuits.

Topics:

- ☆ Modeling and simulation of all sorts of semiconductor devices, including FinFETs, ultra-thin SOI devices, emerging memory devices, optoelectronic devices, TFTs, sensors, power electronic device, widegap semiconductor devices, spintronic devices, tunnel FETs, SETs, carbon-based nanodevices, organic electronic devices, and bioelectronic devices
- ☆ Modeling and simulation of all sorts of semiconductor processes, including first-principles material design and growth simulation of Numerical methods and algorithms, including grid generation, user-interface, and visualization nano-scale f ☆ Metrology for the modeling of semiconductor devices and processes

Plenary Speakers:

- * Augusto Benvenuti, Micron Technology, "Current status and future prospects of non-volatile memory modeling"
- ★ Massimo V. Fischetti, University of Texas at Dallas, "Physics of electronic transport in low-dimensionality materials for future FETs"
- * Kimimori Hamada, Toyota Motor Corporation, "TCAD challenge on development of power semiconductor devices for automotive applications"

Invited Speakers:

- ★ Mario Ancona, Naval Research Laboratory, "Nonlinear thermoelectroelastic simulation of III-N devices"
- ★ Asen Asenov, University of Glasgow, "Progress in the simulation of time dependent statistical variability in nano CMOS transistors"
- ★ Jean-Pierre Colinge, Taiwan Semiconductor Manufacturing Company, "Nanowire transistors: pushing Moore's law to the limit"
- ★ Tibor Grasser, Vienna University of Technology, "Advanced modeling of charge trapping: RTN, 1/f noise, SILC, and BTI"
- ★ Kohji Mitsubayashi, Tokyo Medical and Dental University, "Novel biosensing devices for medical applications"
- ★ Christian Sandow, Infineon Technologies, "Exploring the limits of the safe operation area of power semiconductor devices"
- ★ Mark Stettler, Intel Corporation, "Device and process modeling: 20 years at Intel's other fab"

Workshops:

Two companion workshops will run concurrently prior to the start of the conference on Monday September 8:

- ★ Compact Modeling —Enabling Better Insight of Device Features—
 - Organizer: Mitiko Miura-Mattausch (Hiroshima University)
- ★ Carrier Transport in Nano-Transistors: Theory and Experiments Organizer: Hideaki Tsuchiya (Kobe University) and Yoshinari Kamakura (Osaka University)

Abstract Submission:

Authors are invited to submit a two-page abstract (A4 size or 22×28 cm) including figures. Full submission information is available at the following web page.

https://sites.google.com/site/sispad2014/

Authors of accepted papers will be notified by May 15, 2014. Camera-ready copy of a four-page manuscript will be required from the authors for inclusion in the Conference Proceedings by June 30, 2014.





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